

What is claimed is:

1. A photomask provided with shielding patterns made of shielding metallic thin film on a transparent substrate, wherein the photomask further comprises translucent patterns mainly including tantalum of materials selected from tantalum silicide, tantalum oxide, tantalum nitride or ^amixture thereof.

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2. A photomask as claimed in claim 1, wherein an intermediate layer is provided between translucent pattern layer and shielding pattern layer.

3. A photomask as claimed in claim 2, wherein the intermediate layer is made of silicon oxide.

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